

(b) Amendment to the Claims

Please amend claim 12 as follows. The status of all the claims is listed below.

1. - 11. (Cancelled)

12. (Currently Amended) A plasma treatment apparatus for individually treating a plurality of reactors having different impedances comprising:

a plurality of movable reactors each having an evacuable interior where at least one treatment substrate is set, and having impedances different from each other;

a high-frequency power supply means for supplying high-frequency power into each movable reactor having been internally-evacuated, to cause glow discharge to take place in the movable reactor ~~wherein each of the reactors and the high-frequency power supply means are provided separately;~~

~~a plurality of an impedance regulation means provided correspondingly to the impedances of each of the reactors in order to regulate impedances on the side of each movable reactor and on the side of the high-frequency power supply means~~ on the side of each movable reactor to regulate the impedances of each reactor; and

a moving means for moving each of the movable reactors,
wherein each of the movable reactors and the high-frequency power supply means are provided separately and wherein ~~[[the]]~~ one impedance regulation means

[[are]] is provided between a connecting portion of the high-frequency power supply means on the side of the moveable reactor and an electrode on the side of the moveable reactor.

13. (Previously Presented) The plasma treatment apparatus of claim 12, wherein the substrate is a substrate for an electrophotographic photosensitive member.

14. - 25. (Cancelled)